

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re Application of:

Wu et al.

Serial No.: 10/672,778

Filed: September 26, 2003

For: Atomic Layer Deposition (ALD) Method with
Enhanced Deposition Rate

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) Group Art Unit: 2891

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) Examiner: Smith, Bradley

)
) Confirmation No.: 9717

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) TKHR Docket: 252016-3000

) Top-Team: 0503-8501DUS
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RESPONSE TO FINAL OFFICE ACTION

Mail Stop AF
Commissioner for Patents
P.O. Box 1450
Alexandria, Virginia 22313-1450

Sir:

The FINAL Office Action mailed May 19, 2006 has been carefully considered. In further response thereto, please enter the following amendments and consider the following remarks.